# Beam Test 2012 Update of TASC data analysis by Gabriele Bigongiari

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# Outline

- TASC calibration with muons
- TASC response with electrons beams at 10, 20, 30, 50, 80, 100, 150, 200, 250 and 290 GeV:

total energy deposit longitudinal profile comparison with Fluka and Epics MC simulations energy deposit vs primary particle energy energy resolution variation of APD gain with temperature study of calibration of 250 and 290 GeV electrons as a function of temperature

### TASC calibration : channel calibration with MIPs

- 150 GeV muon beam;
- Use IMC tracking to select particles crossing the PWO crystal under study
- Selection cuts applied on  $\chi^2$  and on fit parameters





- Pedestal (green curve), physics events (blue curve) and MIPs selection (red curve)
- Fit with a landau convoluted with a gaussian (langaus)
- Fitted MPV used as calibration coefficient
- Sigma used to reproduce the channel spread in MC simulation

## TASC calibration - second step: APD High/Low stitching



#### **Electron runs**

- High gain vs Low gain plot in each channel
- fit to a break line
- Fit parameters used to connect the two signal ranges

# **MonteCarlo Simulation of Beam Test**

#### **Beam Test setup**



Beam test apparatus simulated with Fluka

The simulated energy deposit is without any fluctuation caused by a detector

An event-by-event gaussian fluctuation (noise) event-by-event added

The noise of each TASC channel is simulated using the fitted sigma from MIP data

## Data vs MC: Mean Longitudinal Profile at 150 GeV



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# **2<sup>nd</sup> Layer calibration : logs equalization**



- 100 GeV electron runs
- The beam illuminated all three logs
- Each plot is fitted to a gaussian function to obtain the peak value
- The peaks have been equalized to the average

# 2<sup>nd</sup> layer calibration: MC rescaling



MC average longitudinal profile fitted to a  $\Gamma$ -function;

using the fitted curve a conversion factor (ADC to MIP units) for the 2<sup>nd</sup> layer is calculated.

### 150 GeV electrons total energy deposit: Data vs MC



the peaks of two distributions differ less than 1%

the energy resolution of data is ~2% against ~1.7% of MC

that discrepancy probably due to calibration problem in 2<sup>nd</sup> layer



Pulse height in each channel



Pulse height in each channel



Pulse height in each channel



Pulse height in each channel















#### 250 GeV and 290 GeV electrons runs



MIP peak position in each channel depends on the temperature (about -10 ADC/°C)

the calibration table cannot be applied to 250 GeV and 290 GeV electrons because taken at different temperature (greater than 1 °C) wrt previous runs

using muon runs at different temperatures, we measure the MIP peak variation with temperature in each channel

from the fit results, we calculated two calibration tables for 250 and 290 GeV electrons

the RMS of each channel remains stable as the temperature changes;



the peaks of two distributions differ by less 1%;

the energy resolution of data is about 1.8% against 1.4% of MC;



the peaks of two distributions differ by less 1%;

the energy resolution of data is about 1.5% against 1.3% of MC;

# Difference between data e MC



except for 10 GeV electrons, the difference between Data peak and MC peak is always less than 1% (also at 250 and 290 GeV) except for 10 GeV electrons, the difference between Data resolution and MC resolution is always less than 0.5%

# **Energy Deposit vs Beam Energy**



The TASC response is linear: except for 10 GeV electrons, the residual value is always less than 2% (also at 250 and 290 GeV)

# **Energy Resolution vs Beam Energy (1)**



$$f(E) = p_0 \oplus \frac{p_1}{\sqrt{E[GeV]}}$$

# The points at 10 and 20 GeV not used to fit the curves

	P <sub>o</sub>	<b>P</b> <sub>1</sub>
Data	(1.4±0.1)%	(18±1)%
MC	(0.3±0.3)%	(21±1)%

# **Energy Resolution vs Beam Energy (2)**





- low signal to noise ratio
- we introduced a term to take into account the instrumental effects at low energies

$$f(E) = p_0 \oplus \frac{p_1}{\sqrt{E[GeV]}} \oplus \frac{p_2}{E[GeV]}$$

	P <sub>o</sub>	<b>P</b> <sub>1</sub>	P <sub>2</sub>
Data	(1.5±0.1)%	(13±2)%	(81±8)%
MC	(0.4±0.3)%	(21±1)%	(37±17)%

## Fine calibration of 250 GeV electrons (1)





#### **Nominal temperature**

 Strong variation of calibration table wrt temperature used

# Fine calibration of 250 GeV electrons (2)



# Fine calibration of 250 GeV electrons (3)



Sigma of energy distribution as a function of temperature value used to build the calibration card

Energy resolution as a function of temperature value used to build the calibration card

## Fine calibration of 250 GeV electrons (4)



We obtained the best fit between Data e MC using the calibration table built at T = 31.0 °C (the nominal value is 31.1 °C)

## **Fine calibration of 290 GeV electrons (1)**





**Nominal temperature** 

 As in case of 250 GeV electrons, there is a strong variation of calibration table wrt temperature used

# Fine calibration of 290 GeV electrons (2)



# Fine calibration of 290 GeV electrons (3)



used to build the calibration card

build the calibration card

# **Fine calibration of 290 GeV electrons (4)**



We obtained the best fit between Data e MC using the calibration table built at T = 30.7 °C (the nominal value is 30.6 °C)

# **Energy Deposit vs Beam Energy** after fine calibration for 250 Gev and 290 Gev electrons



The TASC response is linear: except for 10 GeV electrons, the residual value is always less than 2% (also at 250 and 290 GeV)

## **Energy Resolution vs Beam Energy** after fine calibration for 250 Gev and 290 Gev electrons



## **Conclusions & Suggestions**

TASC calibration method based on MIP works fine

Good agreement between beam test electron data and FLUKA MC Good TASC linear behaviour up to 290 GeV

**Calibration criticities:** 

possible bias on MIP fitted peaks due to low S/N ratio

a fine monitoring of temperature changes is mandatory

# **Appendix: list of files used**

- 150 GeV muon beam for calibration:
  20120928\_001904\_mu-169
  20120928\_022006\_mu-172
  20120928\_041941\_mu-174
- 100 GeV electron beam used to calibrate 2<sup>nd</sup> layer: 20120928\_221415\_ele100-211 20120928\_233425\_ele100-213 20120929\_000357\_ele100-215 20120929\_104250\_ele100-241

 150 GeV + 200 GeV electron runs used for stitching: 20120929\_024721\_ele150-222 20120929 035339 ele150-224 20120929 045728 ele150-226 20120929 055351 ele150-228 20120929 065237 ele150-230 20120929 145535 ele200-249 20120929\_154957\_ele200-251 20120929\_164448\_ele200-254 20120929 175114 ele200-257 20120929 184809 ele200-259 20120929 194208 ele200-261 20120929 203636 ele200-264 20120929 213939 ele200-266